
Atomic Layer Deposition Applications 6

Editors:

J. W. Elam

Argonne National Laboratory
Argonne, Illinois, USA

S. De Gendt

IMEC
Leuven, Belgium

O. van der Straten

IBM Research
Albany, New York, USA

A. Delabie

IMEC
Leuven, Belgium

A. Londergan

Qualcomm MEMS Technologies
San Jose, California, USA

S. F. Bent

Stanford University
Stanford, California, USA

F. Roozeboom

Eindhoven University of Technology
and TNO Science and Industry
Eindhoven, The Netherlands

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